

2012.04.19

NEW ETCH ETCH RATE AND SELECTIVITY VALUES FOR OXFORD 81

Date	Tool	Chemistry, or Recipe name	Material*	Rate(nm/min)	Selectivity*	Notes
04/19/12	Oxford 80 #2	CHF3/O2	SiO2	40.8	0.9	10 min O2 plasma clean , 10 min season
04/19/12	Oxford 80 #2	CHF3/O2	LSN	63.5	1.22	"
04/19/12	Oxford 80 #2	CHF3/O2	Si3N4	66	1.45	"
04/19/12	Oxford 80 #2	CF4	Si	61	0.56	"
04/19/12	Oxford 80 #2	CF4	SiO2	44	0.36	"
04/19/12	Oxford 80 #2	CF4	LSN	83.3	0.7	"
04/19/12	Oxford 80 #2	CF4	Si3N4	94.6	0.82	"
04/19/12	Oxford 80 #2	SF6/O2	Si	527	5.72	"
04/19/12	Oxford 80 #2	CHF3/Ar	SiO2	37.2	2.4	"
04/19/12	Oxford 80 #2	CHF3/CF4/Ar	SiO2	56.6	1.28	10 min O2 plasma clean, 3 min season